

L Number	Hits	Search Text	DB	Time stamp
1	8392	inspect\$ adj6 (mask or masks or wafer or wafers)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/04 13:17
2	916	(pulsed adj3 laser) near12 (uv or ultraviolet)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/04 13:15
3	14	((inspect\$ adj6 (mask or masks or wafer or wafers)) and ((pulsed adj3 laser) near12 (uv or ultraviolet)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/04 13:16
4	9291	inspect\$ adj6 (mask or masks or wafer or wafers or photomasks or reticle or reticles)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/04 13:17
5	14	((pulsed adj3 laser) near12 (uv or ultraviolet)) and (inspect\$ adj6 (mask or masks or wafer or wafers or photomasks or reticle or reticles))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/04 13:24
6	29	(inspect\$ adj6 (mask or masks or wafer or wafers or photomasks or reticle or reticles)) and (rotat\$ near4 diffus\$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/04 13:25